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- (73) Patentee: Instytut Chemii Fizycznej Polskiej Akademii Nauk, ul. Kasprzaka 44/52, 01-224 Warszawa PL
- (72) Inventor: Aneta Aniela Kowalska, Grodzisk Mazowiecki PL  
Agnieszka Michota Kaminska, Sulejowek PL  
Witold Adamkiewicz, Ciechanow PL  
Marek Tkacz, Bieniewice PL
- (74) Agent: Fenix Legal KB, Stureplan 4C, 4 tr, 114 35, Stockholm SE
- (54) Title: Method of fabricating copper platform for surface enhanced Raman scattering measurements and copper platform for surface enhanced Raman scattering measurements
- (56) Cited documents: ---
- (57) Abstract:

The invention relates to a method of fabrication of a copper platform for surface enhanced Raman scattering measurements, characterised in that it comprises steps wherein:

- copper hydride (CuH) is reduced as a result of a pressing process under increased pressure,
- the prepared platform is cleaned, preferably using concentrated acetic acid (CH<sub>3</sub>COOH).

The invention comprises also a copper platform for surface enhanced Raman scattering measurements, obtained with the above method, preferably for measurements on living cells, where the copper crystallite size is in the range of 30 – 120 nm, and where the copper crystallites are uniformly distributed in the volume of the platform and on its surface.

